

Form PTO-1449 (REV. 8-83)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 122364		APPLICATION NO. 10/520,461	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANTS Takahiro KISHIOKA et al.			
				FILING DATE January 7, 2005		GROUP	

U.S. PATENT DOCUMENTS						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
ACW	1	US 5,919,599	7/6/1999	MEADOR et al.		
ACW	2	US 5,693,691	12/2/1997	FLAIM et al.		
ACW	3	US 6,083,665	7/4/2000	SATO et al.		
ACW	4	US 6,090,531	7/18/2000	MIZUTANI et al.		
ACW	5	US 6,544,717 B2	4/8/2003	HIROSAKI et al.		
ACW	6	US 6,284,428 B1	9/4/2001	HIROSAKI et al.		
ACW	7	US 2001/0049072 A1	12/6/2001	HIROSAKI et al.		

FOREIGN PATENT DOCUMENTS						
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS
ACW	8	JP A 2000-221689 w/ ab & trl	8/11/2001	JAPAN		
ACW	9	JP A 2000-284491 w/ ab & trl	10/13/2000	JAPAN		
ACW	10	JP A 2002-148791 w/ ab & trl	5/22/2002	JAPAN		
ACW	11	JP A 2000-221690 w/ ab & trl	8/11/2000	JAPAN		
ACW	12	JP A 2001-5186 w/ ab & trl	1/12/2001	JAPAN		
ACW	13	JP A 11-84673 w/ ab & trl	3/26/1999	JAPAN		
ACW	14	JP A 2000-010293 w/ ab & trl	1/14/2000	JAPAN		
ACW	15	JP A 10-333336 w/ ab & trl	12/18/1998	JAPAN		
ACW	16	WO 02/069046 A1	2/20/2002	WIPO		

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)		
ACW	17	LYNCH et al., "Properties and Performance of Near UV Reflectivity Control Layers," <i>Proceedings of SPIE</i> , vol. 2195, pp. 225-229 {1994}
ACW	18	TAYLOR et al., "Methacrylate Resists and Antireflective Coatings for 193 nm Lithography," <i>Proceedings of SPIE</i> , vol. 3678, pp. 174-185 {March 1999}
ACW	19	MEADOR et al., "Recent Progress in 193 nm Antireflective Coatings," <i>Proceedings of SPIE</i> , vol. 3678, pp. 800-809 {March 1999}

EXAMINER <div style="text-align: center;">/Amanda C. Walke/</div>	DATE CONSIDERED <div style="text-align: center;">09/05/2006</div>
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Examiner:	Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.
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Date: April 20, 2005